

MAGNETRON SPUTTERING TARGET AND METHOD FOR MANUFACTURING THE

SAME

ABSTRACT

Provided is a target for use in magnetron sputtering.

5 This target can increase, without reducing the content of a
ferromagnetic metal element in the target, the magnetic flux
leakage in magnetron sputtering to a level higher than that of
a conventional target. The target is a magnetron sputtering
target (10) having a ferromagnetic metal element, the
10 magnetron sputtering target comprising: a magnetic phase (12)
containing the ferromagnetic metal element; a plurality of
non-magnetic phases (14,16) that each contain the
ferromagnetic metal element and that are different in
constituent elements or a content ratio of constituent
15 elements; and an oxide phase(18), wherein at least one of the
plurality of non-magnetic phases, namely, a non-magnetic
phases (14) is more finely interdispersed with the oxide phase
(18) than the magnetic phase (12).

20 Fig. 1